

Photomask Japan 2023

The 29th Symposium on Photomask and NGL Mask Technology
From Tuesday, April 25 through Thursday, April 27, 2023

Digital Forum

Symposium Chair:

Prof. Takeo Watanabe
University of Hyogo

Abstract Due Date:
November 30, 2022

Manuscript Due Date:
March 31, 2023

Detailed information will be announced in the 2nd Call for Papers. Manuscripts are required of all accepted applicants and must be submitted in English.

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Photomask Japan 2023 is the 29th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and researchers from Japan, USA, and all over the world in the field of photomasks, NGL masks and related technologies to discuss recent progress, applications, and future trends. The symposium program will feature invited papers, contributed papers, poster sessions, and the popular panel discussion.

Papers are solicited on the following and related topics:

- **Materials for photomasks**
- **Fabrication process steps and equipment for photomasks (developing, etching, cleaning etc.)**
- **Photomask writing tools and technologies including multi-beam EB writer**
- **Tools and technologies for metrology/ inspection/ repair**
- **Technologies and infrastructures for EUVL/ NIL/ FPD masks**
- **EDA, MDP, curvilinear ILT and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and multiple patterning**
- **Photomask-related lithography technologies**
- **NGL mask technologies and their applications: DSA and others**
- **Strategy and business challenges: cost, cycle time and total mask solutions**
- **Patterning technologies for semiconductor and electronic devices**
- **Semiconductor manufacturing technologies**
- **eBeam direct writing and eBeam lithography technologies**
- **Utilizing AI technologies for the efficiency of R&D and HVM**
- **Legacy tools for middle and low-end masks**
- **Photomask and lithography related technologies in academia**

Abstract Submission

All authors are *strongly encouraged* to submit their abstract by the due date, November 30 2022 via the PMJ official website. Abstract submission Web page will be opened in October 2022 at:

<https://www.photomask-japan.org/>

Further information and instructions will be made available at the 2nd Announcement & Call for Papers, which will be published around September 2022.

***Please do not send the abstract by e-mail or facsimile.**